



UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

Teiichirou Chiba *et al.*

Serial No.: 09/492,761

Filed: January 27, 2000

For: SEMICONDUCTOR WAFER

Examiner: C. Chu

Group Art Unit: 2815

RESPONSE UNDER 37 C.F.R. § 1.111

Honorable Commissioner
of Patents and Trademarks
Washington, D.C. 20231

December 13, 2001

Dear Sir:

The following amendments and remarks are submitted in response to the Official Action mailed September 13, 2001. The Official Action set forth a three-month period for response, making this response to one or before December 13, 2001.

Please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please replace the paragraph beginning at page 23, line 15, with the following rewritten paragraph:

-- A plane shape of the notch 1 is as shown by Fig. 2. In plane view, a longest dimension from a side face of the wafer W to a bottom portion of the notch 1 falls in a range of 1 to 1.25 mm, the bottom portion defines a circular